

# Studies of LCLS FEL Divergence

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## Abstract

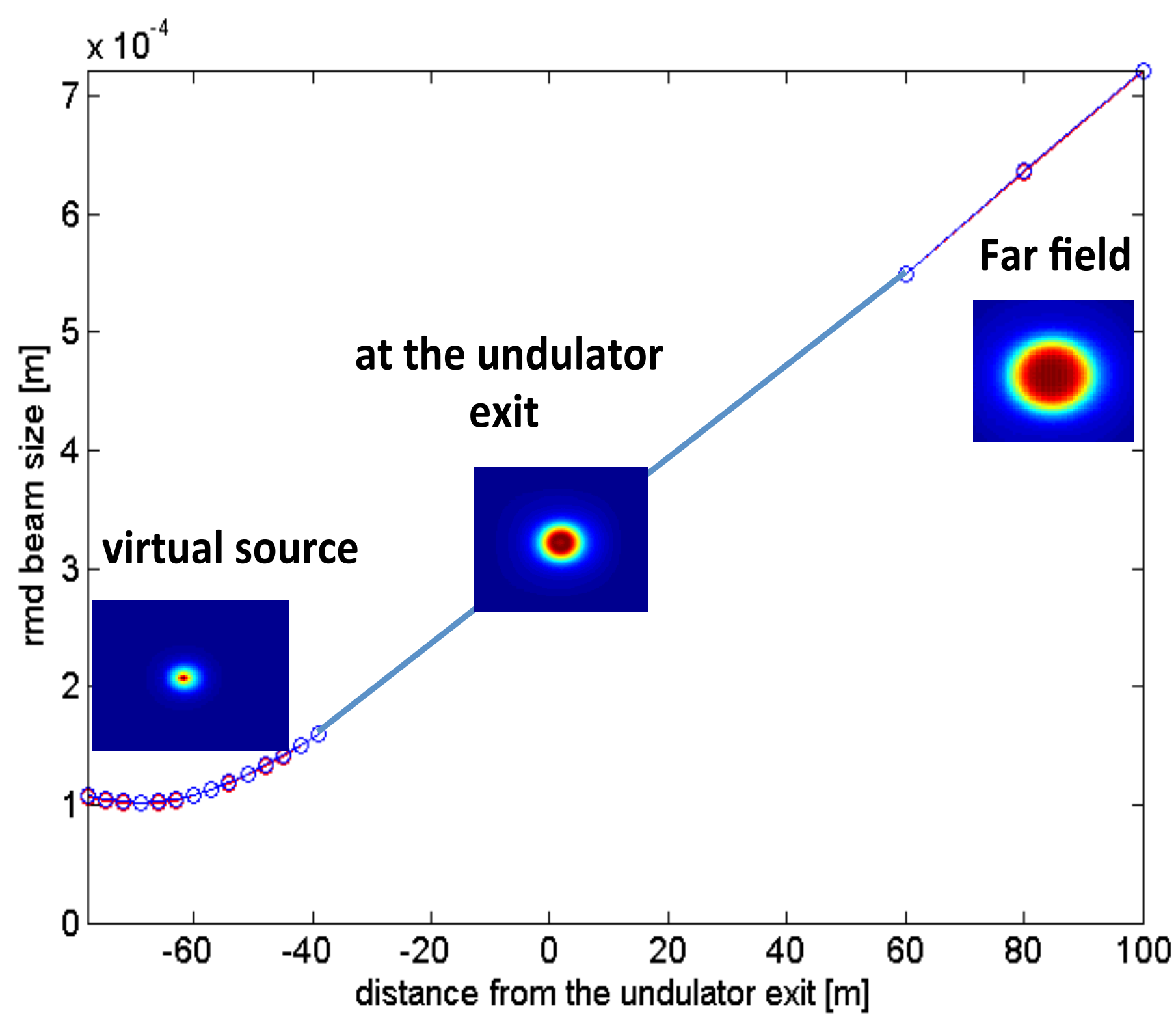
Simulations show various impacts on x-ray divergence. With the motivation to maximize intensity at the focus, these LCLS beam studies were designed to study parameter space and beam qualities impacting divergence, and therefore aperture related clipping and diffraction. With multiple simultaneous users, beam constraints increase, requiring an improving knowledge of the mechanism of impact of changing parameters. These studies have that goal in order to improve beam control.

$$\sigma_D = \sqrt{\lambda L_{1D} / 4\pi} \quad (1)$$

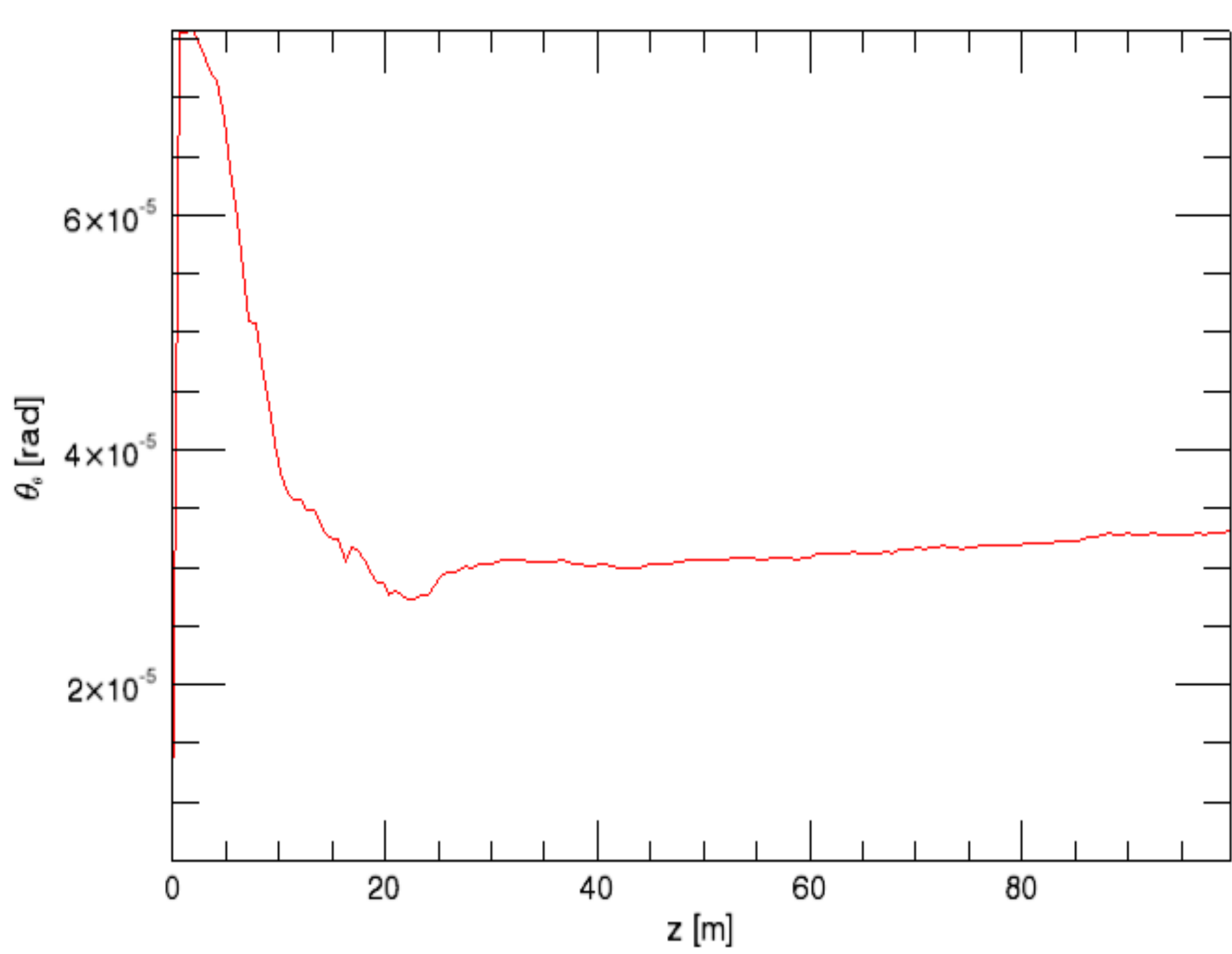
$$\sigma_{ph} \approx \sqrt{\sigma_D \sigma_{el}} \quad (2)$$

$$\sigma_\theta = \lambda / 4\pi \sigma_{ph} \quad (3)$$

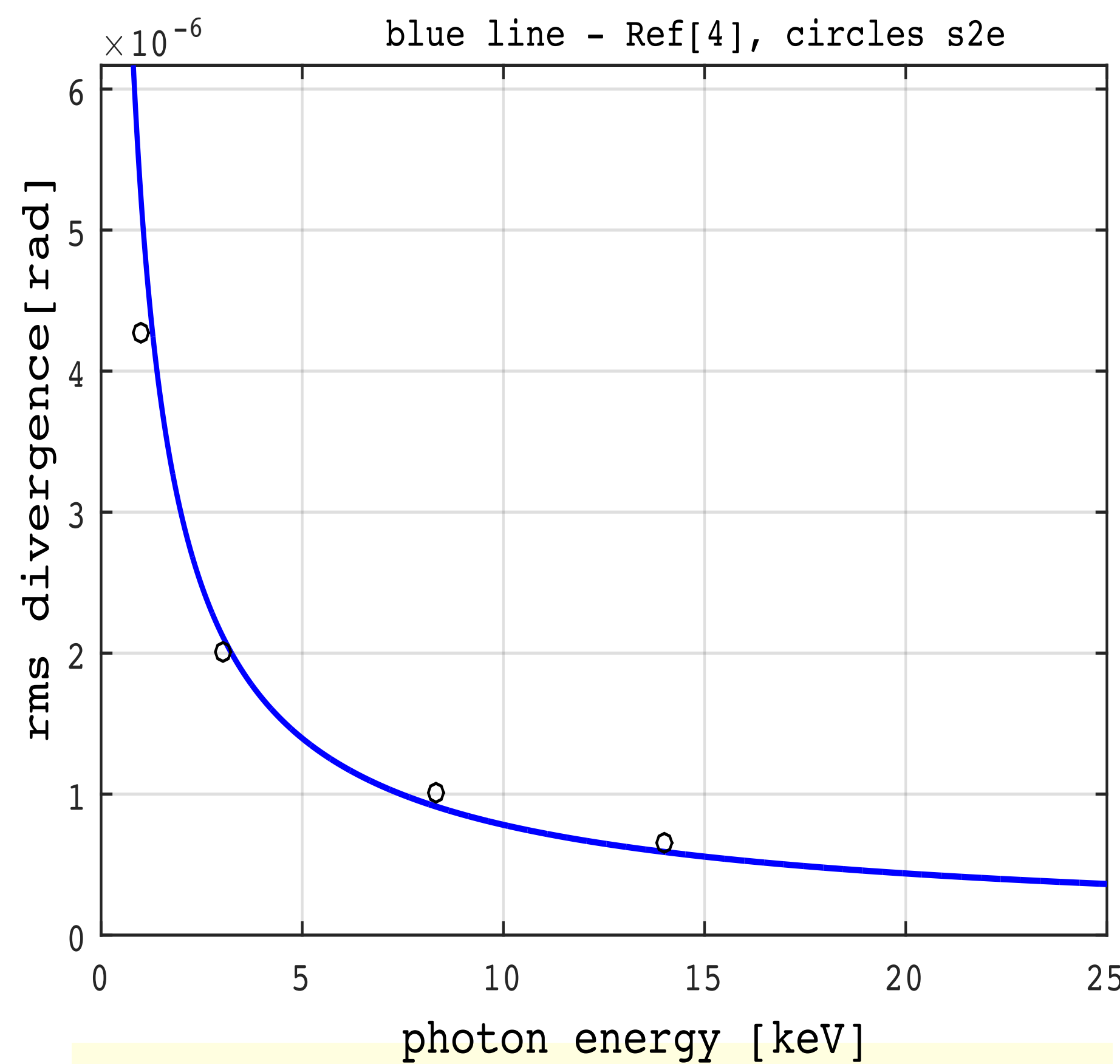
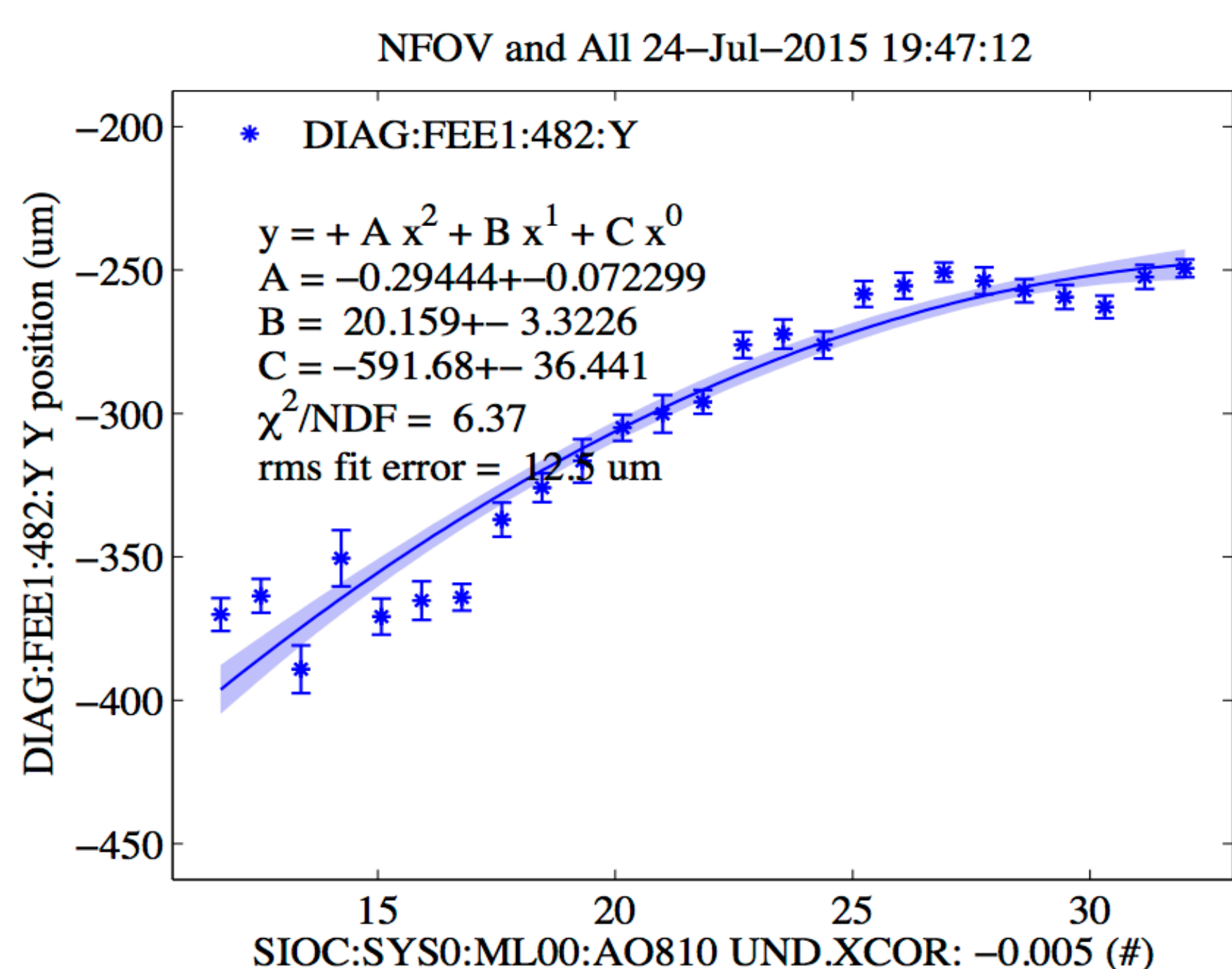
We applied Z. Huang and K. J. Kim approximation, derived in the linear regime, to calculate the photon source size (eq. 2) and the divergence (eq. 3). 1D gain length  $L_{1D}$ , in the equation 1, was generated using the Ming Xie parameterization.



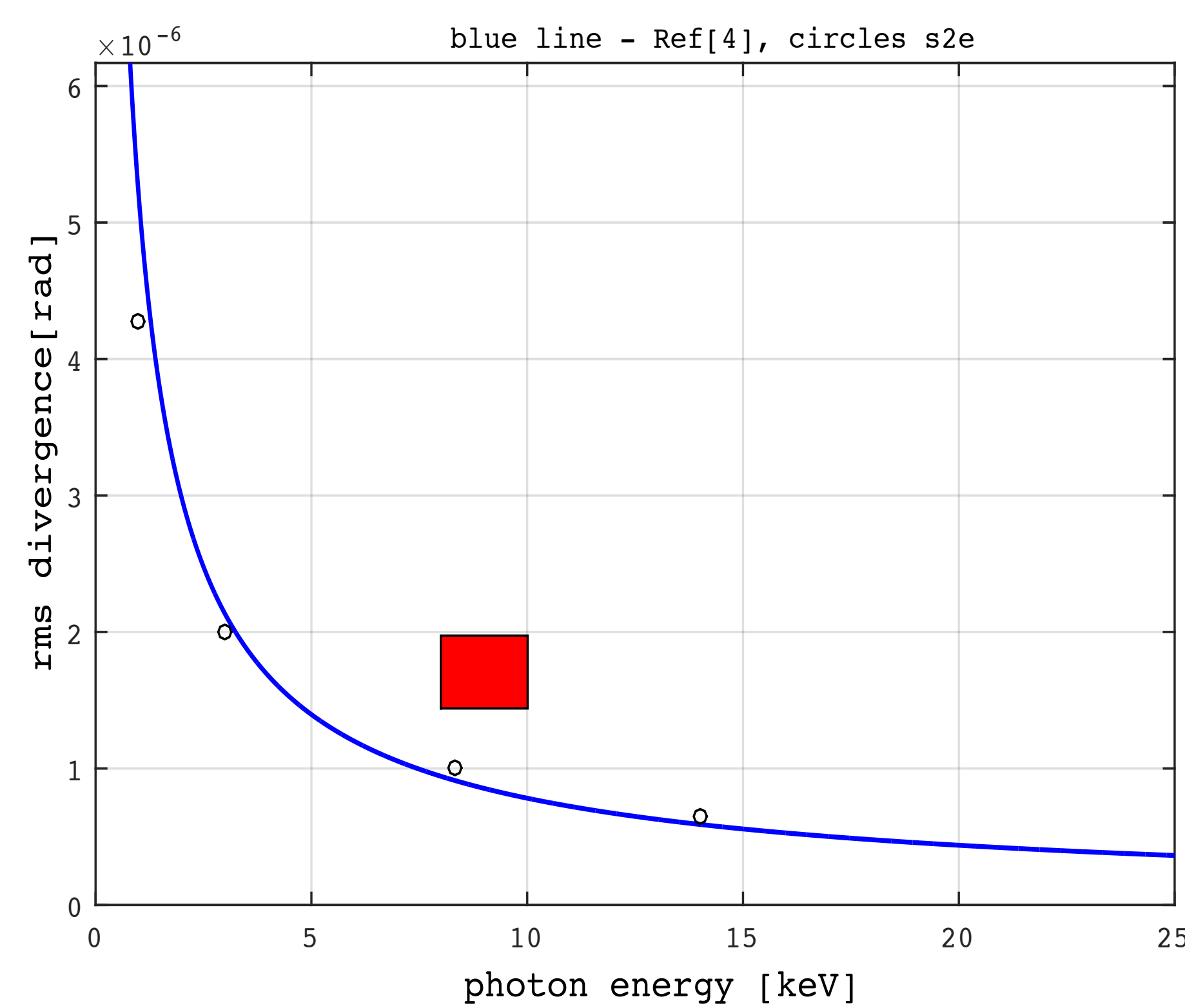
Simulation gives wave front at the exit of the undulator, then it is propagated backward and forward giving the waist (source) and the far field.



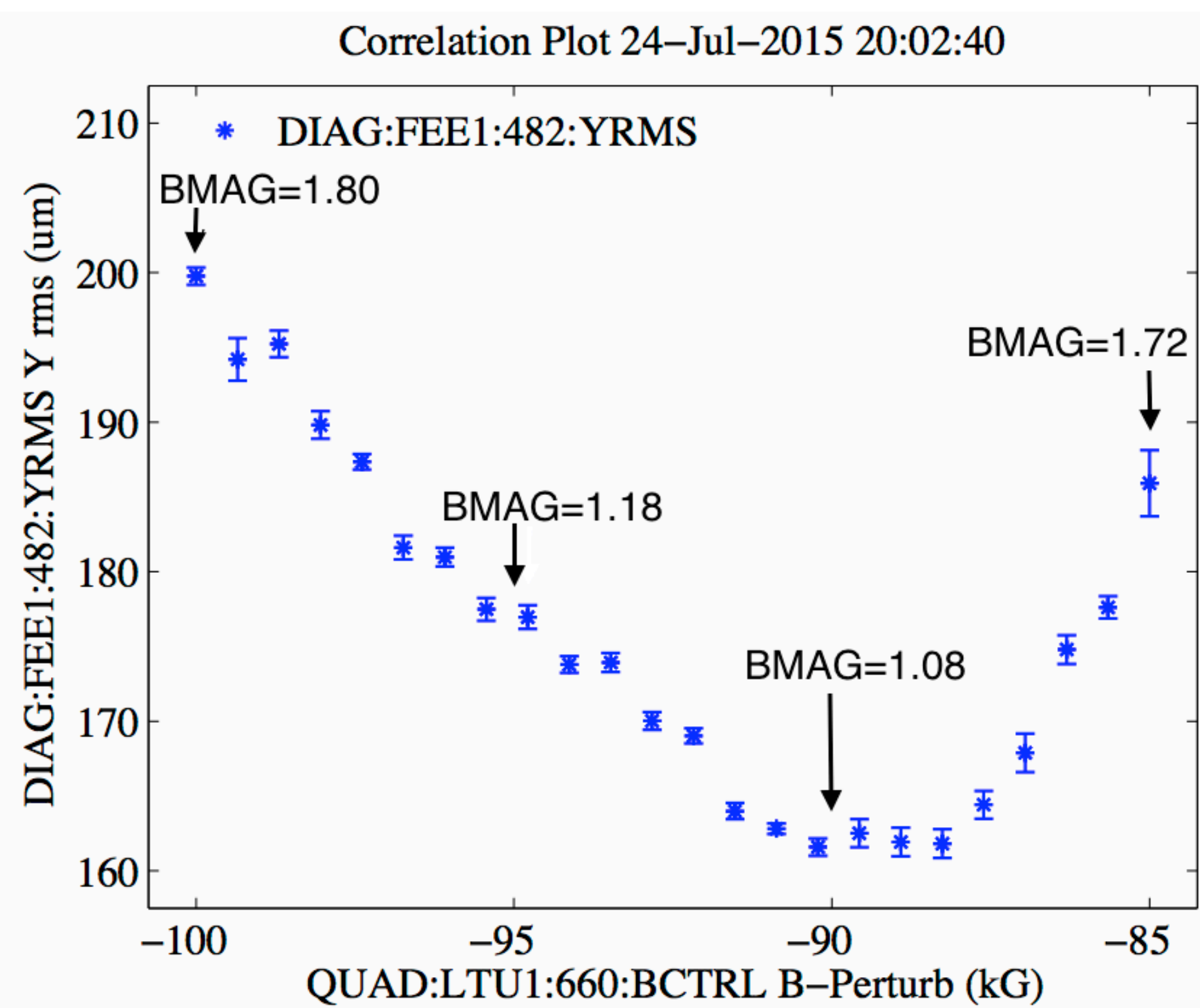
Simulation indicates that at 300 eV there is very small divergence change in the non-linear growth regime. This indicates the HK model should also predict divergence in the non-linear regime.



HK Divergence Model (blue line) compared to start-to-end simulations and forward propagation (circles).

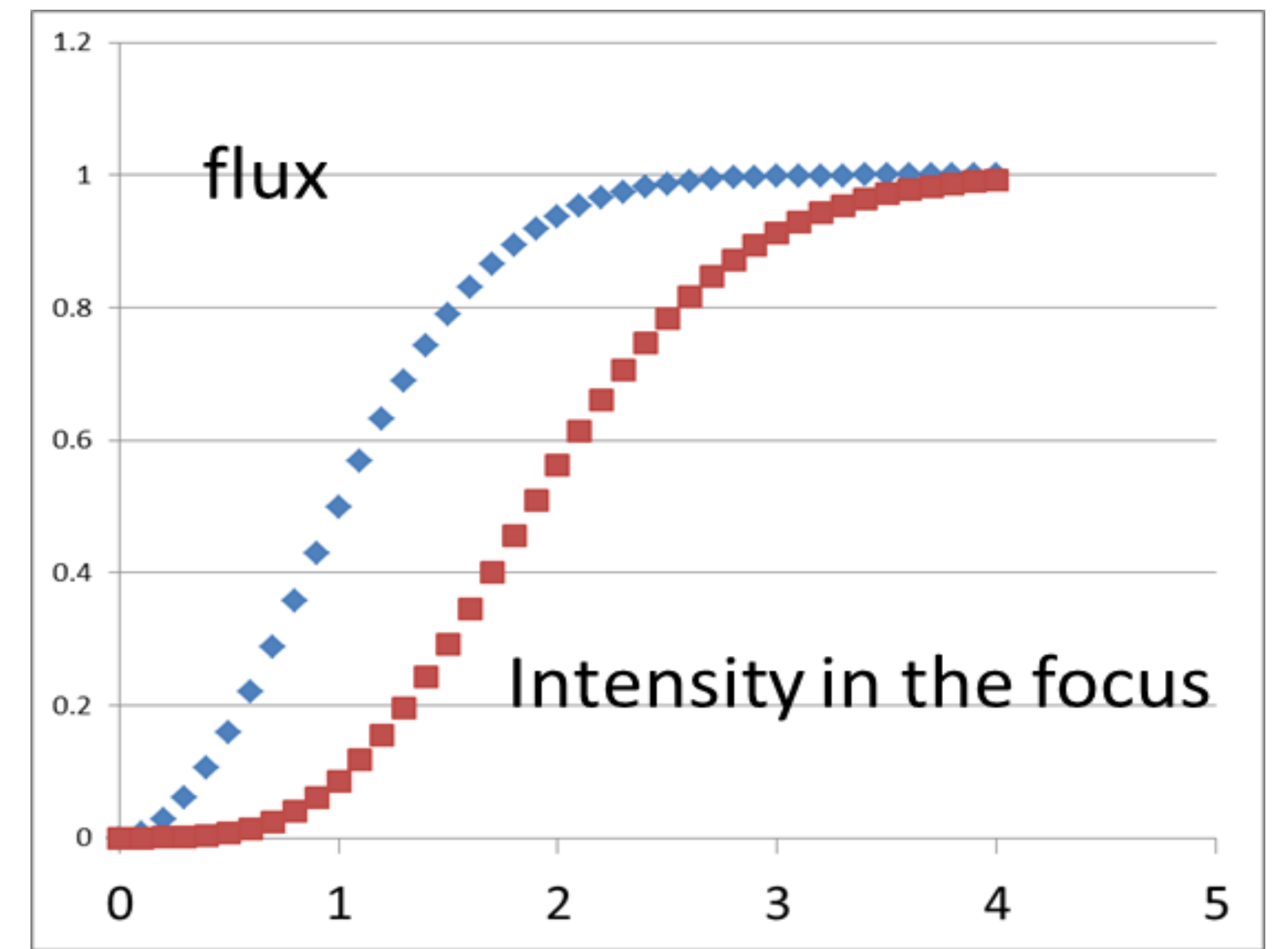


Recent hard x-ray divergence measurements over the past year are represented by the red rectangle.



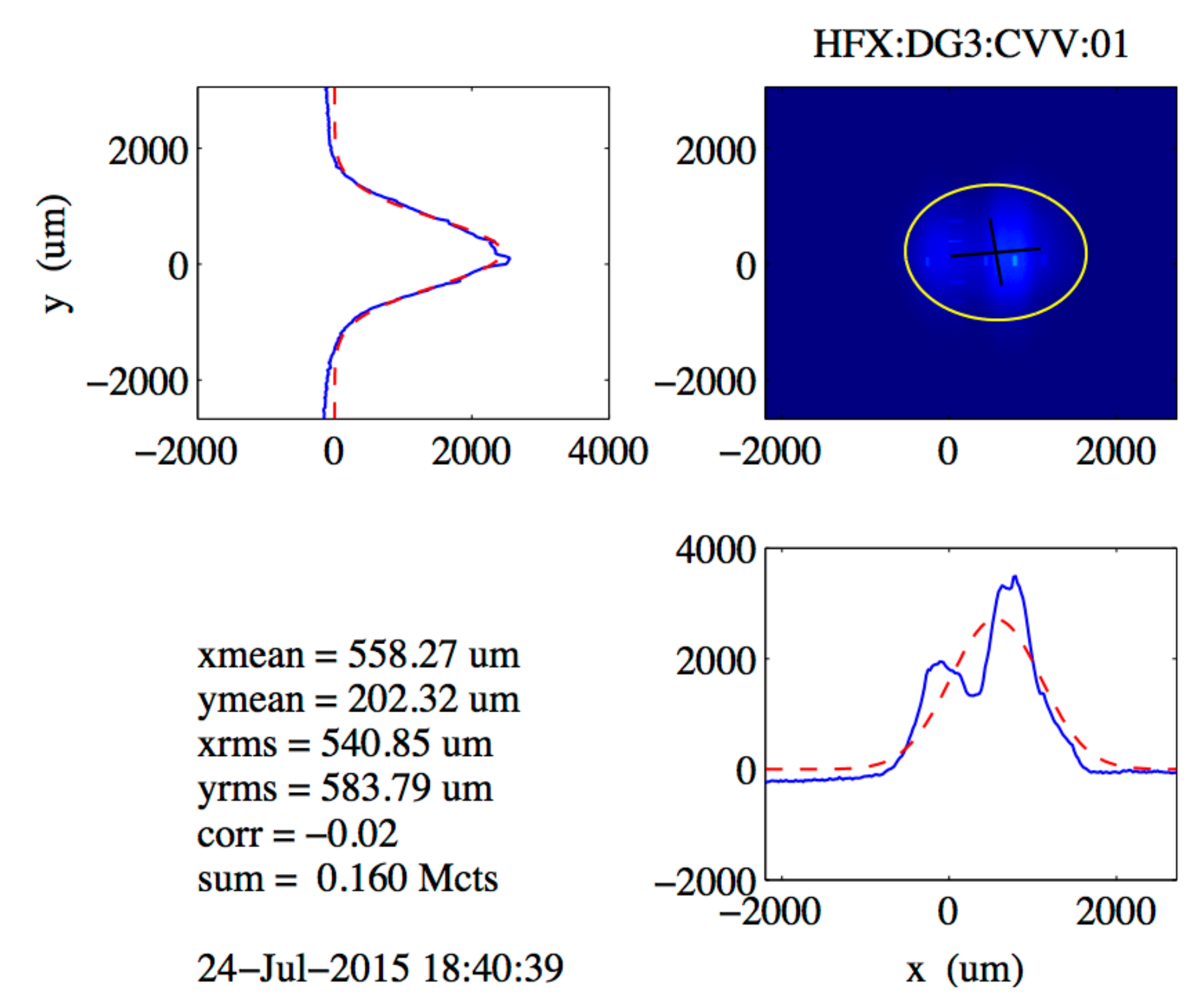
Beam divergence changes with match change in the undulator.

Left: Curvature of the electron orbit in the undulator was measured in the matched, 4 meter gain-length, 8.2 keV condition. Electron beam is kicked at different points to suppress lasing beyond each point. X-ray position is measured at the imager 87 meters after the undulator.

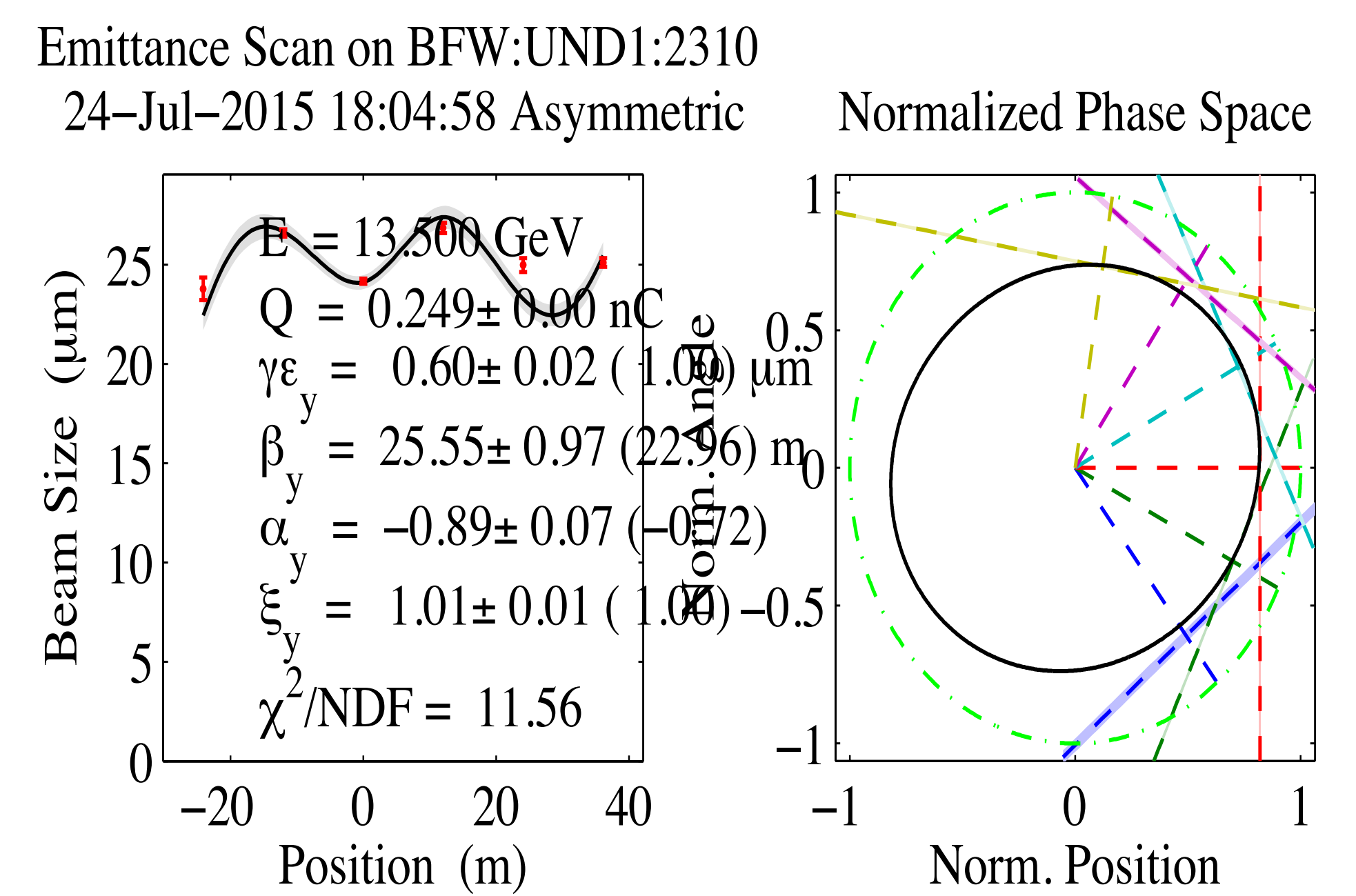


## Acceptance (FWHM)

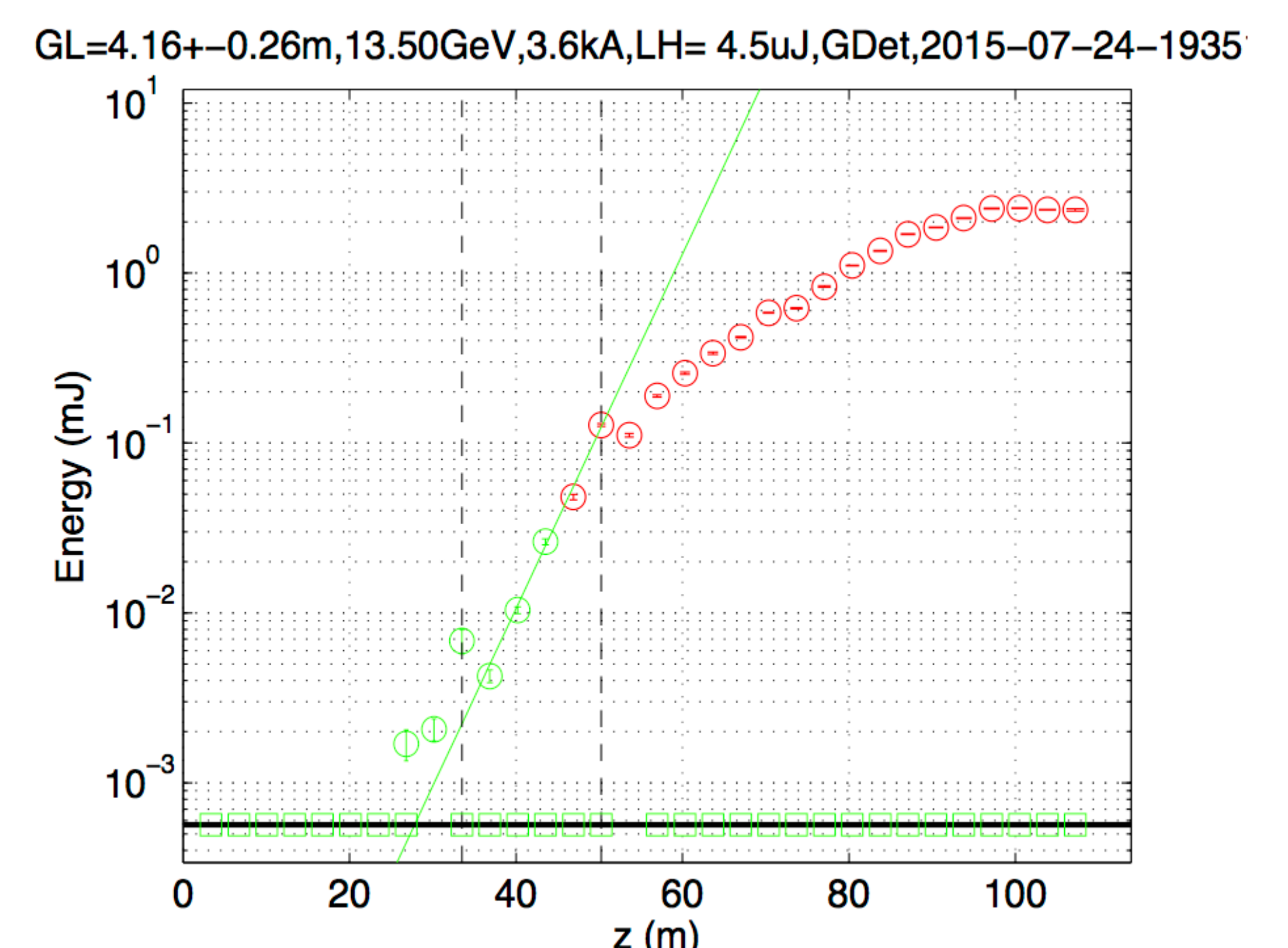
Vertical axis is relative intensity, horizontal axis acceptance of mirror systems cutting in both planes. Blue line is the intensity cut off by mirrors. Red line is the intensity at a downstream focus. Diffraction effects are taken into account.



Beam size measured at the Far Hall 335 meters from the end of the undulator. Energy is 8.2 keV. Note the horizontal distortion is due to mirror figure error and diffraction effects.



Vertical beta measurement in the undulator using 6 "beam finder wires". Beta match parameter is 1.01 +/- 0.01 with perfect being 1.0. Electron beam size at the source point is included in this measurement.



The gain length is measured by a system of gas detector PMTs (photomultiplier tubes) at different high voltage settings to achieve a large dynamic range.